TOTAL ALD SOLUTIONS

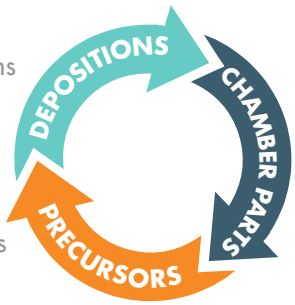
ALD has emerged as a powerful and preferred tool for many industrial and research applications. It is used in the Microelectronics and Nanoelectronics industries including Photovoltaics / Solar and LED's. Precursor suppliers, OEMS, Fabs and cleaning companies have come to rely on ChemTrace® techniques for materials and process characterization.

PRECURSORS ANALYZED:

TDMAS	TBTDET	TEOS	TMPO
BDEAS	TBTEMAT	TEPO	$ZrCl_4$
CCTBA	TCS	$TiCl_4$	DMAS
DIPAS	TDMAT	TMA	$CPCOCO_2$
EDNOMO	TDMA-HF	TMOS	
HCDS	TDMAZC	TMP	
MDNOW	TEB	TMPB	
OCTS	TEMAZ	TMPI	

DEPOSITIONS
Analysis of depositions by DFS™ ICP-MS for In-Film Trace Metals

PRECURSORS
Analysis of precursors for trace metals by ICP-MS/OES

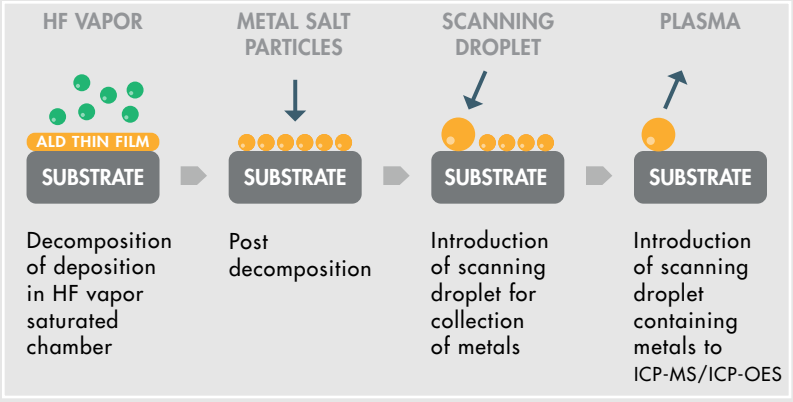


CHAMBER PARTS
Validation of cleaning process for residual metal depositions by CLPE™ ICP-MS & Anions by Ion Chromatography

DFS ICP-MS/OES ANALYSIS

Advanced Wet Chemistry Technique allowing etching of full thickness of deposition across a large surface area.

- Bevel edge analysis
- Fully quantitative
- High sensitivities
- Major metal composition
- 40+ element survey



COMPREHENSIVE NON-DESTRUCTIVE PARTS ANALYSIS

VERIFICATION:

- Trace Metals Analysis
- Particle Counts
- Anions and Cations
- Organics
- Elemental Analysis of Particles

ANALYTICAL TECHNIQUES:

- Controlled Liquid Phase Extraction™ ICP-MS
- Ultrasonic Aided UPW Extraction - Liquid Particle Counter
- UPW Extraction Ion Chromatography
- Solvent Extraction GC-MS and ATD GC-MS
- SEM-EDX

COMPREHENSIVE PART ANALYSIS SUPPORT & SERVICES

NEW AND USED PARTS

FIRST ARTICLE EVALUATION	BASELINING OF PART CLEANLINESS	SPECIFICATION SET UP	ON-GOING VALIDATION OF CLEANLINESS
How clean is clean?	Build statistics	Set control limits	SPC incoming parts

contact us at Info@ChemTrace.com

CHEMTRACE® Solution Based Chemistry™